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PATENT APPLICATION
ATTORNEY DOCKET NO. LMRX-P023/P1130

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: SHIH et al.
Application No.: 10/666,331
Filed: 9/17/2003

Examiner: KORNAKOV, Michail
Group No.: 1746
Confirmation No.: 8374

Title: METHODS FOR CLEANING A SET OF
STRUCTURES COMPRISING YTTRIUM OXIDE IN
A PLASMA PROCESSING SYSTEM

CERTIFICATE OF MAILING
I hereby certify that this correspondence is being deposited with the
US Postal Service as First Class Mail in a postage-paid envelope
addressed to the Commissioner for Patents, P.O. Box 1450,
Alexandria, VA 22313-1450 on April 26, 2005.
Signed: /Alma Fazlic/
Alma Fazlic

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449 may be material to the patentability of the above-identified patent application. Applicants submit the list of these references in compliance with their duty of disclosure pursuant to 37 CFR §§ 1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is believed to be filed before the mailing date of a first Office Action on the merits. If it is determined that fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 50-2284 (Order No. LMRX-P023).

Respectfully submitted,

By: /Joseph Nguyen/
Joseph Nguyen
Reg. No. 37,899



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OTHER DOCUMENTS

Examiner Initials	Cite No.	Description	T
	1	GEORGE, H. Bola, "In-Situ Analysis of High Density Plasma Enhanced Chemical Vapor Deposition of Thin Films," October 13, 1999, 17 slides total	
	2	"Acetone," http://www.wikipedia.org/wiki/Acetone , 2 pages total	
	3	JOHNSON et al., "Reducing PFC gas emissions from CVD chamber cleaning," Solid State Technology, December 2000, 6 pages total	
	4	"Hydrogen Peroxide (H ₂ O ₂): the Amazing Secrets That THEY Don't Want You to Know!," http://www.h2o2-4u.com/ , 6 pages total	
	5	HORIUCHI et al., "In-Situ Chamber Wall Cleaning in Processing Plasmas," 4 pages total	
	6	FRIZ et al., "Coating Materials," pp. 105-130	
	7	YEOH et al., "Photoresist Strip on Orion2.2™ in Via First Dual Damascene Cu Structures," Trikon Technologies, 3 pages total	
	8	"Yttrium Oxide Products: Ideal for Titanium Processing," ZYP Coatings Inc., 8 pages total	
	9	NELSON et al., "Yttrium Oxide Nanoparticles Prepared by Alkalide Reduction," Chem. Mater. 2002, 14, pp. 915-917	
	10	"Chemical of the Week: Ammonia, NH ₃ ," http://scifun.chem.wisc.edu/chemweek/ammonia/ammonia.html , 3 pages total	
	11	"I.Introduction," EE 4283/6283 SiC RIE lab project, MS State University, 6 pages total	
	12	"Thermal Spray Coatings: Nature of Thermal Spray Coatings," 10 pages total, http://www.gordonengland.co.uk/tsc.htm	
	13	NICKERSON et al., "Plasma Cleaning of Medical Devices," Critical Cleaning in Precision Manufacturing, 4 pages total	
	14	SOBOLEWSKI et al., "Electrical Optimization of Plasma-enhanced Chemical Vapor Deposition Chamber Cleaning Plasmas," J. Vac. Sci. Technol. B 16(1), Jan/Feb 1998, pp. 173 - 182	
	15	"Plasma Spray Process," http://www.gordonengland.co.uk/ps.htm , 3 pages total	

Examiner Signature		Date Considered	
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